Transaction Information

Tool ID	FMTK-AF1
Tool Status	Connected
Location	Singapore
Wafer Size	200 mm
Fab Section	Metrology
Tool Available Date	2024-08-15

General Product Information

Vendor Supplier	KLA Tencor
Model	OP2600DUVI
Vintage	1997
Serial No	6454
Asset Description	THERMA-WAVE OP2600UV OPTI PROBE FILM THICKNESS
Software Version	3.0k7
CIM	SECS
Process	Film thickness measurement

Hardware Configuration (Fab)

System Type	Description	Quantity	Status
Handler System	ATM-105	1	OK
Factory Interface	SMIF	2	OK
Options System	NA	0	OK
Others	NA	0	OK
Main System	Main body	1	OK

Hardware Configuration (Subfab / Auxilliary Units)

Description	Quantity	Status
NA	0	OK

Missing/Faulty Parts / Accesorries List

Description	Quantity
NA	0

Tool Pictures

General Main body



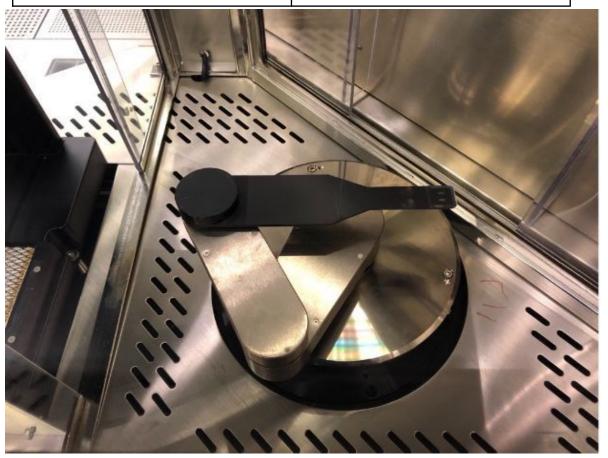
Hardware Fab

Robot & Indexer



Hardware Fab

Robot & Indexer



Manufacture Serial Tool SN



Additional Tool Data Files

FACILITY REQUIREMENTS

Electrical

- 100-200 or 200-240 VAC
- $50 \text{ or } 60 \text{ Hz} \pm 2 \text{Hz}$

Vacuum

• 20-24" Hg (inches of mercury) (normal air pressure at sea level is about 30" Hg)

Air or N2

• 70 -100 PSI, according to the users manual

Humidity

• $30\% - 70\% \pm 2\%$ maximum change per hour

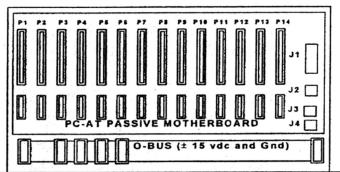
Temperature

20°C ±2°C

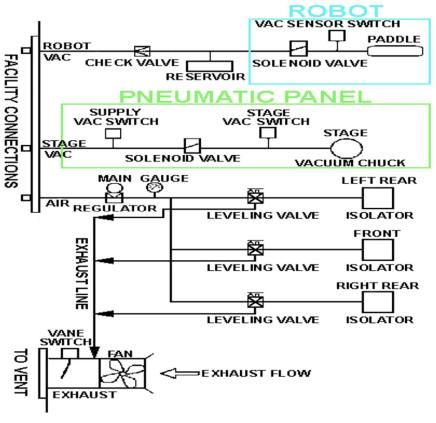
Temperature variation

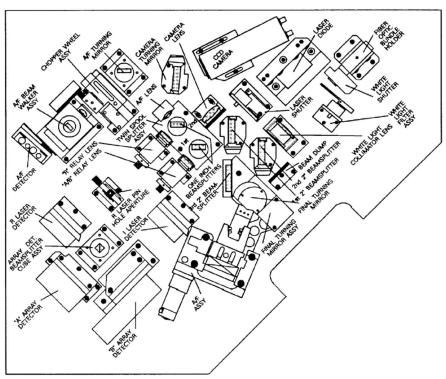
1°C per 24 hour

OP 2600 AT & O Busses



SLOT	CIRCUIT CARD
1	Analog Processor
2	A/D Converter (Data Translation)
3	Autofocus Main PCB
4	Autofocus Driver PCB
5	Stage Driver (PC-23 Compumotor PCB)
6	Empty
7	Digital I/O Controller
8	Light Pen PCB
9	VGA PCB
10	CPU PCB
11	SCSI Controller PCB
12	Empty
13	SECS (Optional)
14	Empty





BEAM PROFILE ELLIPSOMETER

- Measures changes in the polarization of the reflected light.
- Uses a laser for measurements.
- Measurements are made by four photo detectors, a quad cell.
- Measures the mixed polarized components of the reflected light.
- Produces two values, the sum and difference of the photo cells.
- Can be applied to thin films, 0 to 200Å

BEAM PROFILE REFLECTOMETER

- Measures reflected light intensity, as determined by the angle of incidence.
- · Uses a laser for measurements.
- Measurements are made by two array detectors, the A and B arrays.
- Measures two polarized components of the reflected light.
- · Produces two profiles.
- Can be applied to films greater than 100Å

SPECTROMETER

- Measures reflected light intensity, as determined by the lights wavelength.
- Uses a white light for measurements.
- Measurements are made by an array detector, the C array.
- Measures the component wavelengths of the reflected light.
- Produces a full spectrum intensity plot.
- Useful for thick and high index films.